

In the Claims:

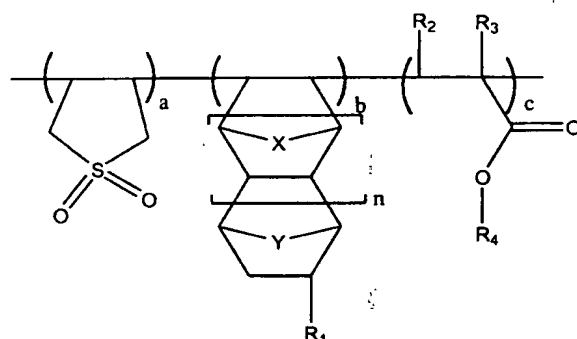
Please amend claims 16, 30 and 35 as follows:

Claims 1-15 (canceled)

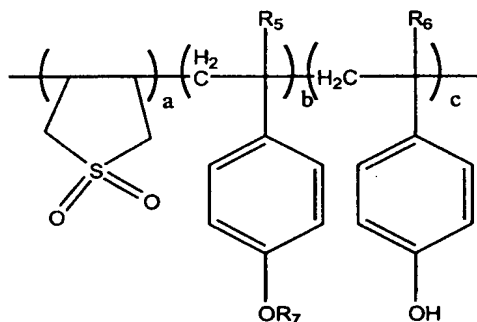
Claim 16 (currently amended) A photoresist composition comprising:

(i) a photoresist polymer comprising a repeating unit selected from the group consisting of Formulas 2 and 3:

Formula 2



Formula 3



wherein  $R_1$  is selected from the group consisting of H, halogen,  $(C_1-C_{20})$  alkyl,  $(C_1-C_{20})$  alkyl with halogen substituent(s),  $(C_1-C_{20})$  alkyl containing an ether group (-O-),  $(C_1-C_{20})$  alkyl with halogen substituent(s) and containing an ether group, and -COOR';

$R_2$ ,  $R_3$ ,  $R_5$  and  $R_6$  are individually selected from the group consisting of H, halogen,  $(C_1-C_{20})$  alkyl,  $(C_1-C_{20})$  alkyl with halogen substituent(s),  $(C_1-C_{20})$  alkyl containing an ether group, and  $(C_1-C_{20})$  alkyl with halogen substituent(s) and containing an ether group;

$R'$ ,  $R_4$  and  $R_7$  are individually acid labile protecting groups;

X and Y are individually selected from the group consisting of  $(C_1-C_{10})$  alkylene, O and S;

n is 0 or 1; and  
the ratio a : b : c falls within the ranges 1-50mol% : 0-50mol% : 0-80mol%,  
wherein at least one of b and c must be present;  
(ii) an organic solvent; and  
(iii) a photoacid generator.

Claim 17 (original) The photoresist composition according to claim 16,  
wherein the photoacid generator is selected from the group consisting of  
phthalimidotrifluoromethane sulfonate, dinitrobenzyltosylate, n-decyl disulfone and  
naphthylimido trifluoromethane sulfonate.

Claim 18 (original) The photoresist composition according to claim 17,  
wherein the photoacid generator further comprises a compound selected from the  
group consisting of diphenyl iodide hexafluorophosphate, diphenyl iodide  
hexafluoroarsenate, diphenyl iodide hexafluoroantimonate, diphenyl p-  
methoxyphenylsulfonium triflate, diphenyl p-toluenylsulfonium triflate, diphenyl p-  
isobutylphenylsulfonium triflate, diphenyl p-tert-butylphenylsulfonium triflate,  
triphenylsulfonium hexafluorophosphate, triphenylsulfonium hexafluoroarsenate,  
triphenylsulfonium hexafluoroantimonate, triphenylsulfonium triflate,  
dibutylphenylsulfonium triflate and mixtures thereof.

Claim 19 (original) The photoresist composition according to claim 16,  
wherein the photoacid generator is present in an amount ranging from about 0.05 to  
about 10% by weight of the photoresist polymer.

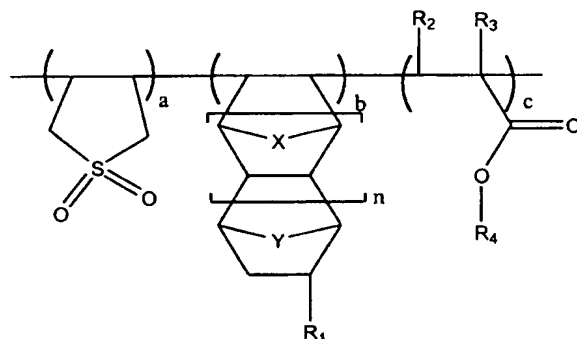
Claim 20 (original) The photoresist composition according to claim 16,  
wherein the organic solvent is selected from the group consisting of methyl 3-  
methoxypropionate, ethyl 3-ethoxypropionate, propylene glycol methyl ether acetate,  
cyclohexanone, 2-heptanone, ethyl lactate and mixtures thereof.

Claim 21 (original) The photoresist composition according to claim 16,  
wherein the organic solvent is present in an amount ranging from about 500 to about  
2000% by weight of the photoresist polymer.

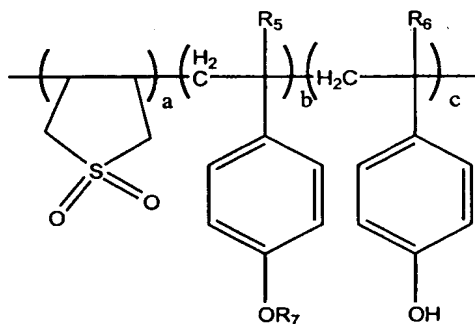
Claims 22-29 (canceled)

Claim 30 (currently amended) A photoresist polymer comprising a repeating unit selected from the group consisting of Formula 2 and Formula 3:

Formula 2



Formula 3



wherein  $R_1$  is selected from the group consisting of H, halogen,  $(C_1-C_{20})$  alkyl,  $(C_1-C_{20})$  alkyl with halogen substituent(s),  $(C_1-C_{20})$  alkyl containing an ether group (-O-),  $(C_1-C_{20})$  alkyl with halogen substituent(s) and containing an ether group, and -COOR';

$R_2$ ,  $R_3$ ,  $R_5$  and  $R_6$  are individually selected from the group consisting of H, halogen,  $(C_1-C_{20})$  alkyl,  $(C_1-C_{20})$  alkyl with halogen substituent(s),  $(C_1-C_{20})$  alkyl containing an ether group, and  $(C_1-C_{20})$  alkyl with halogen substituent(s) and containing an ether group;

$R_1$ ,  $R_4$  and  $R_7$  are individually acid labile protecting groups;

X and Y are individually selected from the group consisting of  $(C_1-C_{10})$  alkylene, O and S;

n is 0 or 1; and

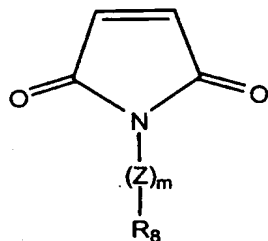
the ratio a : b : c falls within the ranges 1-50mol% : 0-50mol% : 0-80mol%,  
wherein ~~at least one of b and c~~ if the repeating unit is Formula 2, b must be present.

Claim 31 (previously presented) The photoresist polymer according to claim 30, wherein the repeating unit comprises one or more of substituent(s) which are selected from the group consisting of halogen, (C<sub>1</sub>-C<sub>20</sub>) alkyl, (C<sub>1</sub>-C<sub>20</sub>) alkyl with halogen substituent(s), (C<sub>1</sub>-C<sub>20</sub>) alkyl containing an ether group, and (C<sub>1</sub>-C<sub>20</sub>) alkyl with halogen substituent(s) and containing an ether group.

Claim 32 (previously presented) The photoresist polymer according to claim 30, wherein the acid labile protecting group is selected from the group consisting of 2-methyl 2-adamantyl, hexafluoro isopropyl, 8-ethyl 8-tricyclodecanyl, tert-butyl, tetrahydropyran-2-yl, 2-methyl tetrahydropyran-2-yl, tetrahydrofuran-2-yl, 2-methyl tetrahydrofuran-2-yl, 1-methoxypropyl, 1-methoxy-1-methylethyl, 1-ethoxypropyl, 1-ethoxy-1-methylethyl, 1-methoxyethyl, 1-ethoxyethyl, tert-butoxyethyl, 1-isobutoxyethyl and 2-acetylmenth-1-yl.

Claim 33 (previously presented) The photoresist polymer according to claim 30, wherein the repeating unit further comprises a monomer of Formula 4.

Formula 4



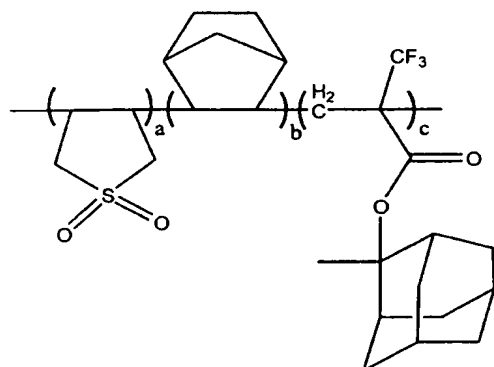
wherein, R<sub>8</sub> is selected from the group consisting of H, halogen, (C<sub>1</sub>-C<sub>20</sub>) alkyl, (C<sub>1</sub>-C<sub>20</sub>) alkyl with halogen substituent(s), (C<sub>1</sub>-C<sub>20</sub>) alkyl containing an ether group, and (C<sub>1</sub>-C<sub>20</sub>) alkyl with halogen substituent(s) and containing an ether group;

Z is O or S; and

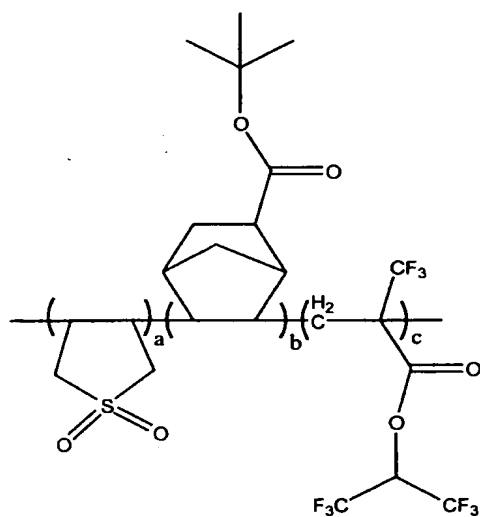
m is 0 or 1.

Claim 34 (previously presented) The photoresist polymer according to claim 30, wherein the repeating unit is represented by Formulas 2a to 2d or Formula 3a:

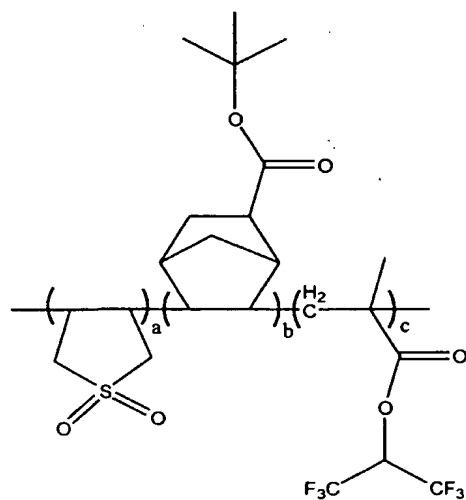
Formula 2a



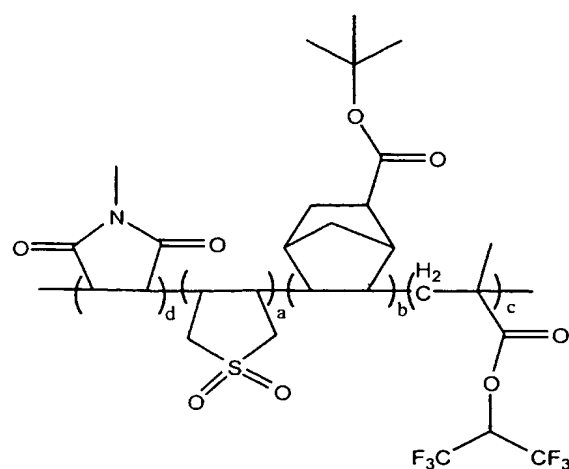
Formula 2b



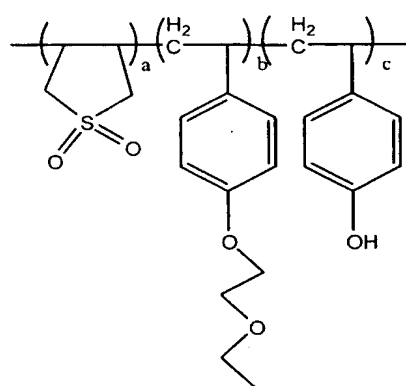
Formula 2c



Formula 2d

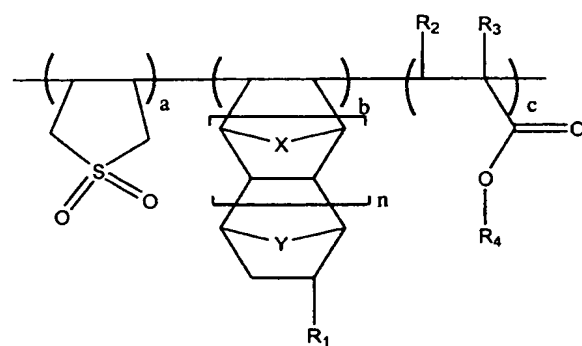


Formula 3a

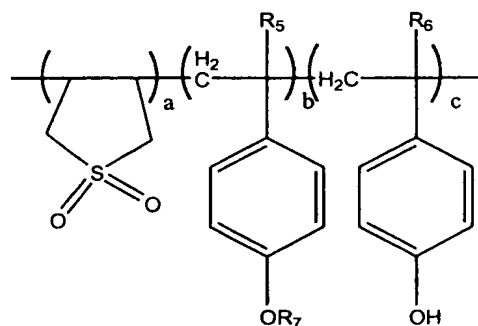


Claim 35 (currently amended) A photoresist polymer comprising a repeating unit selected from the group consisting of Formula 2 and Formula 3:

Formula 2



Formula 3



wherein  $R_1$  is selected from the group consisting of H, halogen,  $(C_1-C_{20})$  alkyl,  $(C_1-C_{20})$  alkyl with halogen substituent(s),  $(C_1-C_{20})$  alkyl containing an ether group (-O-),  $(C_1-C_{20})$  alkyl with halogen substituent(s) and containing an ether group, and -COOR';

$R_2$ ,  $R_3$ ,  $R_5$  and  $R_6$  are individually selected from the group consisting of H, halogen,  $(C_1-C_{20})$  alkyl,  $(C_1-C_{20})$  alkyl with halogen substituent(s),  $(C_1-C_{20})$  alkyl containing an ether group, and  $(C_1-C_{20})$  alkyl with halogen substituent(s) and containing an ether group;

$R_1$ ,  $R_4$  and  $R_7$  are individually acid labile protecting groups;

X and Y are individually selected from the group consisting of  $(C_1-C_{10})$  alkylene, O and S;

n is 0 or 1; and

the ratio a : b : c falls within the ranges 1-50mol% present in an amount up to and including 50mol% present in an amount up to and including 80mol% and wherein if the repeating unit is Formula 2, b must be present.